

# CHESSY

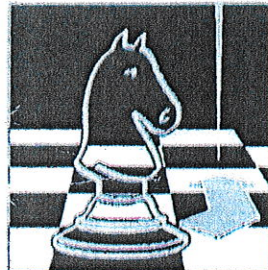
Precise SEM test sample for universal applications

## PLANO GMBH

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## The structure

There are more than 1,6 million gold squares of 1  $\mu\text{m}$  size on silicon forming a 4-fold checkerboard pattern in an area of 5 mm square. The smallest metric checkerboard has a size of 10 x 10  $\mu\text{m}$ . Such checkerboards form larger metric checkerboards of 100 x 100  $\mu\text{m}$  - these again form checkerboards of 1 mm square. Finally such 1 mm squares are arranged in the same manner covering a field of 5 mm square. The edges of the empty corners in the 100  $\mu\text{m}$  checkerboards are additionally marked. The surrounding frame is 10  $\mu\text{m}$  wide and it has an outer side length of 5.04 mm.

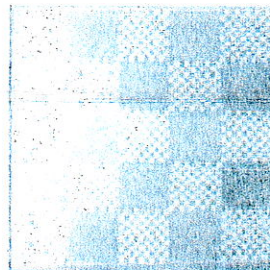


The pattern was directly written in a resist by electron beam lithography using the ZBA 23H from Leica Microsystems Lithography GmbH, and pattern transfer in the gold layer was done by ion beam etching.

## Applications

### Imaging

- Calibration of SEM magnification in all ranges between 20x and 50,000x
- Check of equal scaling in X and Y
- Check of orthogonality and distortion
- Resolution test at high magnification on the edges of the gold squares



### Motorized stages

- Measurement of reproducibility using stored positions
- Calibration of readings in X and Y
- Calibration of stage orthogonality
- Measurement of absolute positioning accuracy

### Experimental EBL (use with Raith pattern generator ELPHY Plus or Quantum)

- Generation of metric writing fields between 10  $\mu\text{m}$  and 5 mm square via mark recognition and alignment
- Measurement of SEM distortion at any magnification via mark recognition on different places
- Check of defocusing in outer areas